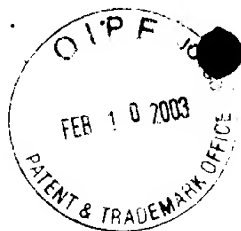


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TC 1700

PATENT

1765  
#210  
- 1/103  
(1765)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re U.S. Patent Application

Applicant: Kozo Nakamura, et al.

Serial No.: 09/856,212

Filed: May 18, 2001

For: Production Method For Silicon Single Crystal )  
And Production Device For Single Crystal )  
Ingot, And Heat Treating Method For Silicon )  
Single Crystal Water )

) Group Art Unit: 1765

)

) I hereby certify that this correspondence

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) envelope address to: Assistant

) Commissioner of Patents, Washington, DC

) 20231, on February 4, 2003.

)

)

) Gerald T. Shekleton  
) Gerald T. Shekleton Reg. No. 27,466 Date

)

Examiner: Matthew J. Song

AMENDMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

The Office Action of November 5, 2002 has been carefully reviewed and the following  
amendments/remarks are made in response thereto.

**IN THE CLAIMS**

Please amend Claims 1-5, 7 and 9-11 as follows:

- (1)
1. (Amended) A method for producing a relatively defect free silicon single crystal  
ingot under the following conditions: